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UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Eiji NATORI

Application No.: 09/819,687

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Filed: March 29, 2001

Docket No.: 109121

For:

METHOD AND DEVICE FOR MANUFACTURING CERAMICS, SEMICONDUCTOR DEVICE, AND PIEZOELECTRIC DEVICE

## **PRELIMINARY AMENDMENT**

Director of the U.S. Patent and Trademark Office Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

## IN THE CLAIMS:

Please replace claims 35, 37, 39, 40, 45, 46, 50 and 51 as follows:

35. (Amended) The method of fabricating ceramics as defined in claim 1, wherein at least one of the active species and the electromagnetic wave is fed to part of a substrate.

37. (Amended) The method of fabricating ceramics as defined in claim 3, wherein the first ceramic film is formed by a coating method, the liquid source misted chemical deposition (LSMCD), the chemical vapor deposition (CVD), or a sputtering method.

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39. (Amended) The method of fabricating ceramics as defined in claim 1, wherein the ceramic film or the second ceramic film is formed of ferroelectrics.

40. (Amended) The method of fabricating ceramics as defined in claim 1, wherein the ceramic film or the second ceramic film is formed at a temperature of

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less than 600°C.